





United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMSSIONER OF PATENTS AND TRADEMARKI Washington, D.C. 2023

APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO
09/467,992	12/20/1999	LEONARD FORBES	303.389US2	3099
21186 7	590 04/17/2003	•		
	-	DESSNER & KLUTH, P.A.	EXAMINER	
P.O. BOX 2938 MINNEAPOLI			LEE, EU	IGENE
			ART UNIT	PAPER NUMBER
			2815	
		•	DATE MAILED: 04/17/2003	

Please find below and/or attached an Office communication concerning this application or proceeding.

		am.	
	Application No.	Applicant(s)	
	09/467,992	FORBES ET AL.	
 Office Action Summary 	Examiner	Art Unit	
	Eugene Lee	2815	
Th MAILING DATE of this communication a	ppears on the cover she t	vith the correspondence address	
Period for Reply A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a relif to period for reply is specified above, the maximum statutory perions. Failure to reply within the set or extended period for reply will, by state. Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	I. 1.136(a). In no event, however, may a epply within the statutory minimum of th od will apply and will expire SIX (6) MC ute, cause the application to become	reply be timely filed irreply be timely filed irreply. NTHS from the mailing date of this communication. NBANDONED (35 U.S.C. § 133).	,
Status			
1) Responsive to communication(s) filed on 03			
,	This action is non-final.		
3) Since this application is in condition for allocal closed in accordance with the practice under Disposition of Claims	wance except for formal m er <i>Ex parte Quayle</i> , 1935 C	atters, prosecution as to the merits is .D. 11, 453 O.G. 213.	
4) Claim(s) 17-19,22,23,25-27,29 and 31-51 is	/are pending in the applica	tion.	
4a) Of the above claim(s) is/are withdo	rawn from consideration.		
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>17-19,22,23,25-27,29 and 31-51</u> is/	are rejected.		
7) Claim(s) is/are objected to.			
8) Claim(s) are subject to restriction and	/or election requirement.		
Application Papers			
9) ☐ The specification is objected to by the Examin			
10) The drawing(s) filed on is/are: a) acc			
Applicant may not request that any objection to			
11)☐ The proposed drawing correction filed on		disapproved by the Examiner.	
If approved, corrected drawings are required in			
12) ☐ The oath or declaration is objected to by the I	Examiner.		
Priority under 35 U.S.C. §§ 119 and 120			
13) Acknowledgment is made of a claim for fore	ign priority under 35 U.S.C	. § 119(a)-(d) or (t).	
a) ☐ All b) ☐ Some * c) ☐ None of:			
1. Certified copies of the priority docume			
2. Certified copies of the priority docume			
3. Copies of the certified copies of the prapplication from the International Example * See the attached detailed Office action for a limit of the certified of the copies of the properties of the properties of the properties of the properties of the certified copies of the properties of the	Bureau (PCT Rule 17.2(a))		٠
14) Acknowledgment is made of a claim for dome	stic priority under 35 U.S.C	. § 119(e) (to a provisional application)	•
a) ☐ The translation of the foreign language parts) ☐ Acknowledgment is made of a claim for dome			
Attachment(s)			
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449) Paper No(s 	5) Notice of	v Summary (PTO-413) Paper No(s) f Informal Patent Application (PTO-152)	
S. Patent and Trademark Office			

Art Unit: 2815

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 17 thru 19, 31 thru 33, 37, 38, 41 thru 46, 48, 49, and 51 are rejected under 35
 U.S.C. 103(a) as being unpatentable over Pfiester 4,761.385 in view of Kanetaki et al. 4,906,590
 Pfiester discloses (see, for example, FIG. 1) a memory cell comprising a lateral transistor 56, source/drain regions 54, semiconductor material layer (body region) 32, trench capacitor 50, substrate (first plate) 34, capacitor plate (second plate of polycrystalline material) 66, and dielectric layer (insulator layer) 60. A contact from the capacitor plate extends to the source/drain region. The substrate is integral to either source/drain region since the source/drain region is part of the substrate. Pfiester does not disclose a first micro-roughened polysilicon surface and a second micro-roughened polysilicon surface. However, Kanetaki discloses (see. for example, FIG. 2) a trench capacitor containing two plurality of hollows (roughened surfaces). In column 1, lines 11-*, Kanetaki states that the plurality of hollows increases the electrode area without increasing the planar area. Therefore, it would have been obvious to one of ordinary skill in the art at the time of invention to include the plurality of hollows (roughened surfaces) in Pfiester's invention in order to increase the electrode area without increasing the planar area.
- 3. Claims 22 thru 25, 34 and 39 are rejected under 35 U.S.C. 103(a) as being unpatentable over Itoh 4,920,389 in view of Kanetaki et al. 4,906,590. Itoh discloses (see, for example, FIG_

Art Unit: 2815

8(k)) a memory cell array structure comprising memory cells wherein an individual memory cell comprises bit lines 222, word lines 234, a low electric resistance region (first source/drain region) 232, high electric resistance semiconductor layer (body region) 204, low electric resistance semiconductor layer (second source/drain region) 202 and a highly electroconductive layer (second plate) 216. In column 13, lines 18-32, Itoh discloses the low electric resistance semiconductor layer 202 serving as a first electrode (first plate) of a capacitor as well as a source region. In column 10, lines 31-41, Itoh discloses the highly electroconductive layer comprising polycrystalline silicon. Itoh does not disclose an etch-roughened surface. However, Kanetaki discloses (see, for example, FIG. 2) a trench capacitor containing two plurality of hollows (roughened surfaces). In column 1, lines 11-*, Kanetaki states that the plurality of hollows increases the electrode area without increasing the planar area. Therefore, it would have been obvious to one of ordinary skill in the art at the time of invention to include the plurality of hollows (roughened surfaces) in Itoh's invention in order to increase the electrode area without increasing the planar area.

Claims 26, 27, 29, 35, 36, 40, 47, and 50 are rejected under 35 U.S.C. 103(a) as being 4. unpatentable over Itoh '389 in view of Kanetaki et al. '590 as applied to claims 22-25, 34 and 39 above, and further in view of Wahlstrom 5,396,452. Itoh in view of Kanetaki does not disclose a row decoder and column decoder so as to selectively access the cells of an array. However, Wahlstrom discloses (see, for example, FIG. 2) a dynamic random access memory comprising memory cells arranged in an array wherein word lines (WL) are arranged orthogonal to bit lines (BL). In FIG. 1, Wahlstrom shows a row decoder and a column decoder which access the memory cells according to the row and column addresses applied. It would have been obvious to

Art Unit: 2815

one of ordinary skill in the art at the time of invention to have a column and row decoder in order to form a memory cell array wherein the individual memory cells may be accessed easily.

Response to Arguments

5. Applicant's arguments filed 2/03/03 have been fully considered but they are not persuasive.

Regarding the appellants' argument on page 5, middle paragraph that Pfeister does not disclose a transistor having source/drain regions formed "outwardly" from a substrate, the Examiner respectfully disagrees. The limitation in claim 17 states "a transistor formed in a layer of semiconductor material outwardly from a substrate,". Such a limitation is clearly shown in FIG. 1 of Pfeister wherein Pfeister discloses a transistor 56 comprising source/drain regions 54 in a layer of semiconductor material and a gate electrode that is formed outwardly from a substrate 42. Therefore, since the gate electrode is part of the transistor, Pfiester does indeed show "a transistor formed in a layer of semiconductor material outwardly from a substrate,".

Regarding the appellant's argument on page 5, last paragraph that there is no reason for combining Itoh and Kanetaki because Itoh has no mention of an etch-roughened surface and Kanetaki has no mention of a vertical transistor, the Examiner respectfully disagrees. Clearly, Itoh and Kanetaki disclose the same semiconductor art, a trench capacitor. In FIG. 8(k), Itoh shows a capacitor portion comprising regions 202, 210 and 216. In FIG. 2, Kanetaki shows a capacitor portion comprising regions 4, 6, and 1. Therefore, since Itoh and Kanetaki involve the same semiconductor art, it is clearly obvious to one of ordinary skill in the art that Itoh and Kanetaki can be reasonably combined. Regarding appellant's argument that Kanetaki does not

Art Unit: 2815

0015

disclose a vertical transistor, this is not critical to whether a capacitor's electrode can have an etch-roughened surface or whether Itoh and Kanetaki can be combined. What is critical is that Kanetaki clearly states (see column 1, lines 11- *) that a capacitor's electrode area can be increased by roughening its surface and therefore, since Itoh also discloses a capacitor, it would have been obvious to also roughen the surface of Itoh's electrode like Kanetaki in order to increase its area.

Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Art Unit: 2815

INFORMATION ON HOW TO CONTACT THE USPTO

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Eugene Lee whose telephone number is 703-305-5695. The examiner can normally be reached on M-F 8-5.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie C. Lee can be reached on 703-308-1690. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Eugene Lee April 11, 2003

SHEILAY. CLARK
PRIMARY EXAMINER

Page 6